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**THE**  
PARTNER  
FOR CUSTOMIZED WET PROCESS  
EQUIPMENT



## RinseStep *Drying*

Cleaning system for various cleaning and drying applications

## BENEFITS

- Cleaning system for various cleaning and drying application
- Different configuration (table top, stand alone or double stack)
- Designed for substrates up to 200 mm
- Space saving, movable footprint
- Superior reliability
- Unique modular construction
- Extremely maintenance-friendly
- Easy to use and operate



**RinseStep**, a compact and durable cleaning tool, that is available as manual or fully automated system. It excels wherever flexibility and variable process requirements are needed. Thanks to the stability and user-simplicity this system is an enriching addition to any fab.

**RinseStep** is capable of handling different wafer sizes.

Carefully engineered software solutions provide operators with the best control possible.

**RinseStep** is the choice of industry partners everywhere where reproducibility, stability and user ease are critical to profitability. In its standard configuration, **RinseStep** is capable of running all of the common substrate cleaning and drying processes.

## FEATURES & BENEFITS

### Application

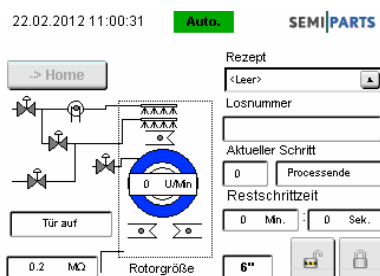
For cleaning after many different processes

### General Features

- **RinseStep** maxi for wafers up to 200 mm
- Processes single 25-wafer batches
- Standard high or low profile cassette
- The optionally build-in resistivity sensor controls the wafer cleaning process
- Cold or hot nitrogen assist the wafers drying process
- The spinning rotor is very easy changeable

### Graphical User Interface

- Based on PLC with 5,7" color touchpanel
- Recipe editor for up to 10 recipes with 10 steps
- Multi-tiered password levels



### General Installation data

Dimensions:	depending of configuration (L x D x H)
Nom. Voltage:	230 VAC
Rated frequency:	50 Hz / 60 Hz
Nominal current:	1 x 16 A (etc.)

### Available training

Operation, maintenance and process

### Available options

- Chamber ionization
- DI-Water reclaim
- Resistivity monitoring
- Ready for robot loading
- Available as table top, stand alone or double stack
- SECS /GEM
- DI-water heating system
- Available also in stainless steel
- Fire suppression system for solvent applications
- special carriers